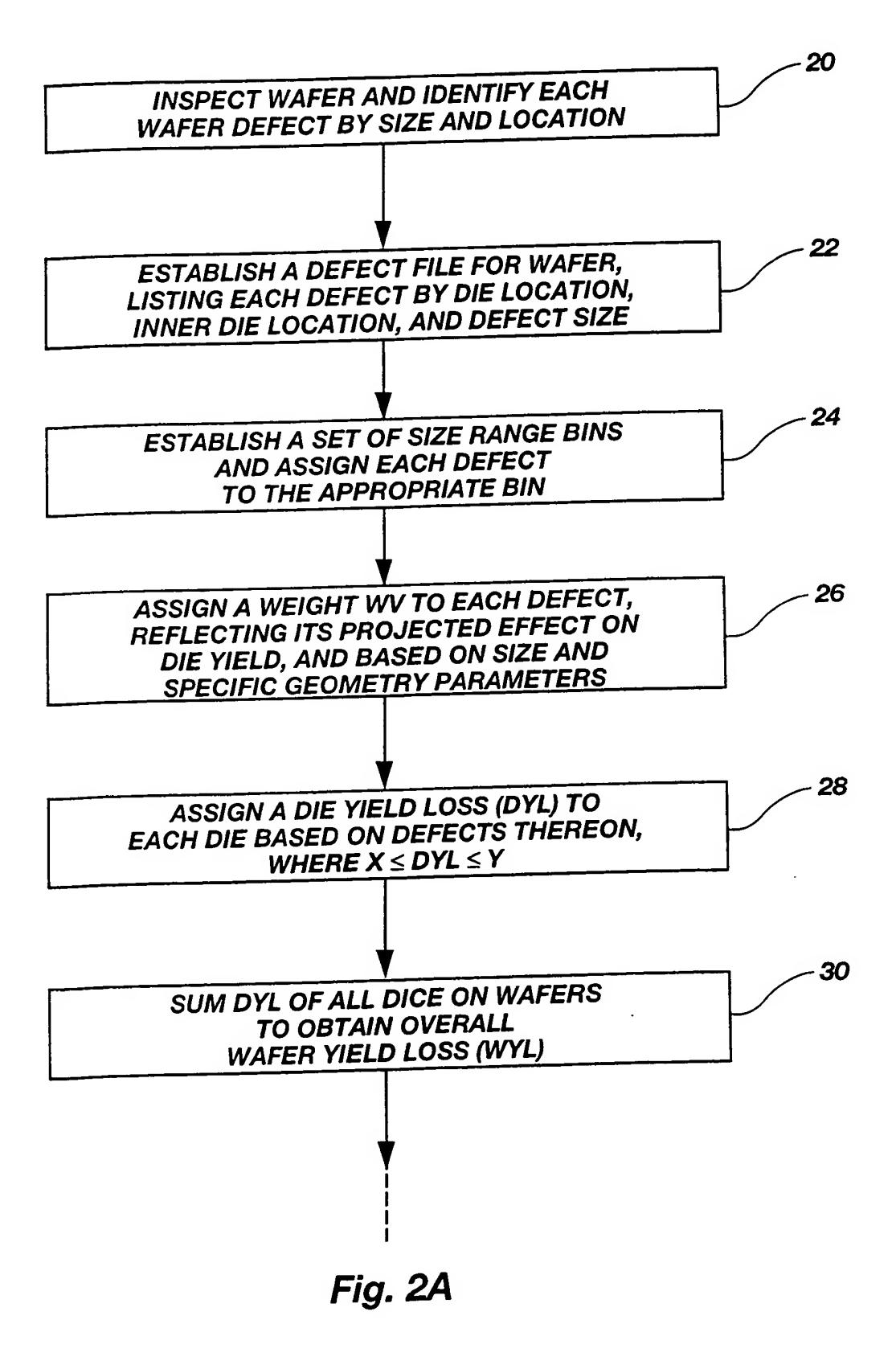
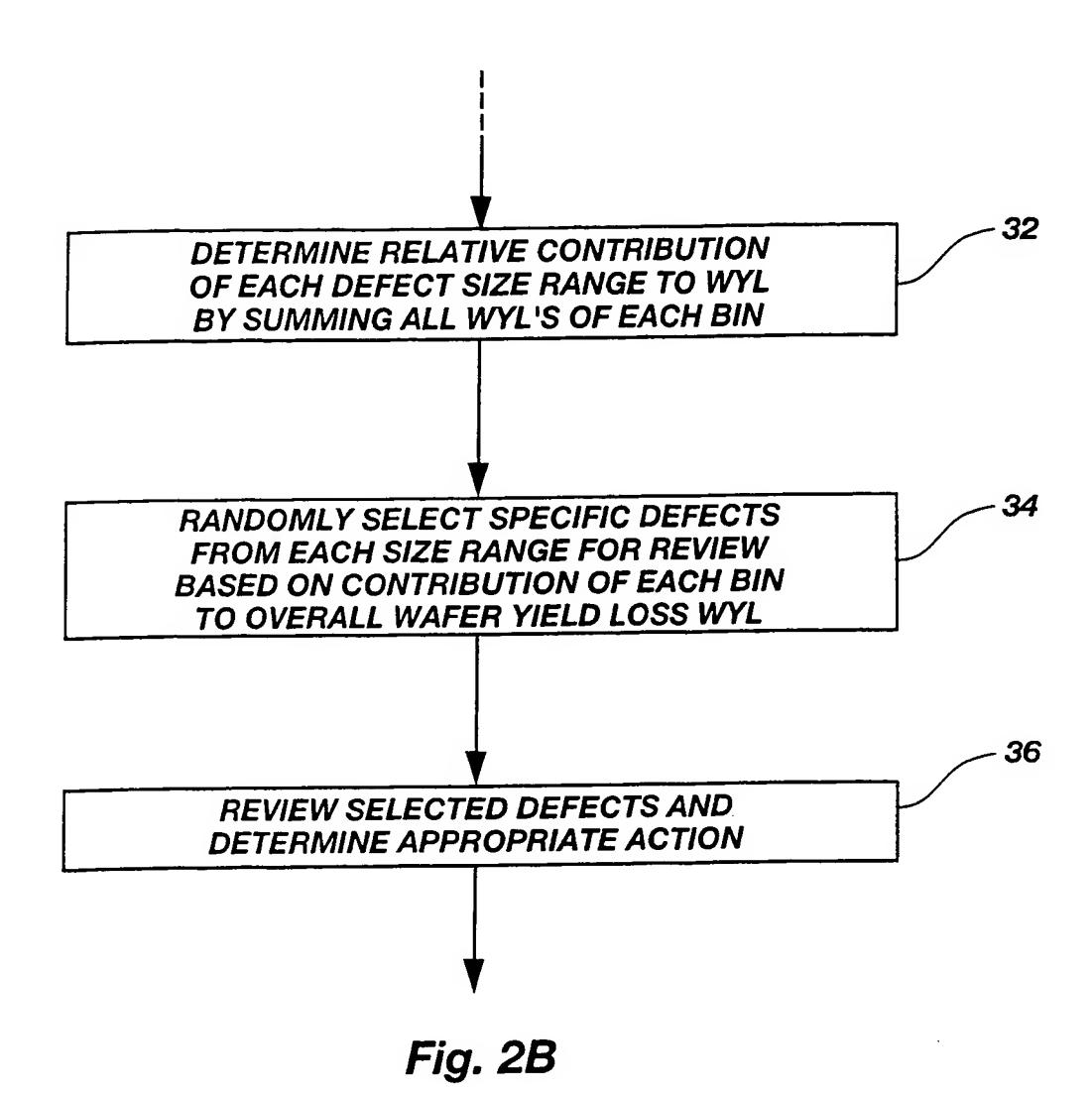


Fig. 1





Lot No. Wager No. Date Inspection Level

S	0	8	က	0	5	2	12
Ъ	0.005	0.153	0.216	0.027	0.439	0.159	1.000
D	0.005	0.141	0.199	0.025	0.404	0.146	0.920
WYL	39.4	34.0	31.7	38.6	23.6	33.8	39.6
% of Total	2.9	46.6	34.0	0.8	10.9	4.6	100.0
# Defects	7	111	81	8	26	11	238
Defect Size	0.0-0.5 µm	0.5-1.0 µm	1.0-2.0 µm	2.0-4.0 µm	4.0-8.0 µm	> 8.0 µm	
Bin No.	-	~	m	4	ري ريا	9	Tota/

Fig. 3

DEFECT REVIEW SHEET

PART TYPE:

DATE:

DEFECTS SAMPLED:

LOT NO: WAFER ID: STEP ID: TOOL ID:

OPERATOR: TIME IN: TIME OUT:

PROJECT NO:

PREDICTED WAFER YIELD LOSS WYL + 39.6 TOTAL DEFECT COUNT = 238

BIN#		1	2			3			4		5	<u></u>		6		
SIZE	0.0-0.5		0.5-1.0		1.0-2.0		2.0-4.0		4.0-8.0			> 8.0				
WYL	39.4		34.0		31.7			38.6		23	23.6		33.8			
# DEFECTS		7	1	11		8	1	2		26			11			
	ID	P	ID	P		ID	P		ID	P	ID	P		ID	P	
			183	2	V	64	2	V			13	1	V	162	1	Ţ
			213	2	V	205	2	V			83	1		192	1	
						226	2	V	/		194	1				
											206	2				
											225	2	M			

ســـــــــــــــــــــــــــــــــــــ	AMPLES	DECODIDATION	
DIE	DEFECT ID	DESCRIPTION	_
			

DEFECT TYPE	DESCRIPTION	TOTAL
1	Block etch	5
2	Lower Level Contamination	7
3		
4		
5		
6	CANNOT FIND	

Fig. 4